

INFORMATION DISCLOSURE CITATION

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Applicant	Hiroshi NOMURA et al.		
Filing Date	Herewith	Prior Group:	2851

U.S. PATENT DOCUMENTS						
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
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	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
AM	11-237310	08/1999	Japan			No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
AM	T.A. Brunner et al., "QUANTITATIVE STEPPER METROLOGY USING THE FOCUS MONITOR TEST MASK", Optical/Laser Microlithography VII, Timothy A. Brunner ed., Proc. SPIE, Vol. 2197, pp 541-549 (1994).
AM	J.P. Kirk et al., "APPLICATION OF BLAZED GRATINGS FOR DETERMINATION OF EQUIVALENT PRIMARY AZIMUTHAL ABERRATIONS", Optical Microlithography XII, Luc Van den Hove ed., Proc. SPIE, Vol. 3679, 70-76 (1999)
AM	Kirk, "ASTIGMATISM AND FIELD CURVATURE FROM PIN-BARS," March 6-8, 1991, SPIE, 1463:282-291

Examiner	Alex Mathews	Date Considered	12-9-2004
*Examiner:	Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		
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